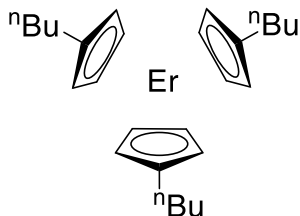


Catalog # 68-7000 Tris(n-butylcyclopentadienyl)erbium(III) (99.9%-Er) (REO)



Thermal Behavior:

- Boiling point: 230-240°C/0.1 Torr [1]
- Vapor pressure: 1.0 Torr/200°C

Technical Notes:

1. ALD/CVD precursor and dopant for erbium thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Er ₂ O ₃	ALD	130°C	3.75-7.5 Torr	O ₃	200-400°C	2

References:

1. [J. Electron. Mater. 1994, 23, 1269](#)
2. [Chem. Vap. Deposition 2014, 20, 217](#)